

Beyond silicon electronics-FETs with nanostructured graphene channels with high on-off ratio and highmobility

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Research Centre for Integrated Systems Nanotechnologies and Carbon Based Nanomaterialsopened in dec.2015







Graphene oxide/PEDOT:PSS on PET de 40 µm;

Equipments for : CVD for growing graphene; ALD; dielectric growth, MBE , metal deposition + Raman and FTIR spectroscopy in a 240 m² clean room with class 1000 , and some areas with class 100. 5 millions Euro investments (UE)



My life with graphene

Graphene ink-Nanointegris

Graphene flakes



2007



2007 from Manchester Univ. Prof. A. Geim and dr. Peter Blake 4 inch graphene wafer on HR Si – Graphene Supermarket 4 inch graphene wafer on HR Si – Graphenea,Spaian

Towards 6 inch wafer



First CVD graphene grown in IMT Bucharest, january 2016

2012



GRAPHENE ELECTRONICS CONUNDRUM : HIGH MOBILITY AND HIGH ON-OFF RATIO

•Graphene electronics was almost abandoned because the key electronic device – the graphene field-effect transistor (GFET), cannot be switched on and off due to the absence of a bandgap.

•How to solve the conundrum?

•GFET with a nanopatterned channel is a high-mobility, high on-off ratio FET.

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SEM image of a nanopatterned GFET channel with 2 µm.

$$E_g=0.16 \text{ eV}$$

March

Barcelona (Spain)

nanohole array with a period of 100 nm and a diameter of 20 nm the corresponding bandgap is about 0.16 eV, but this parameter increases to 0.2 eV if the nanohole diameter becomes 30 nm.





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(a)



90 GFETs on a graphene chip cut from a 4 inch graphene wafer (CVD growth and transfer -Graphenea)-40 % are working very well







Drain current vs drain voltage characteristics of a nanoperforated GFET at various gate voltages indicated in the inset

- the drain current tends to saturate at some gate voltages, e.g. at 1 V and -1 V

- a clear negative differential resistance region (NDR) appears at = -3 V and -4 V.



(a)













on/off



 $g_{D}(L) = g_{d0} \exp(-L/L_{loc})$

Strong localization L_{loc} =1.9µm



Long room temperature localization and phase coherence lengths (8 µm) could be explained by the nonuniform nanohole diameters in the transverse direction, which induces charge carrier focusing/guiding along the middle part of the channel such that the charge carriers avoid the boundaries of the channels and the associated strong recombination centers. These non-uniformities in the hole diameters are induced by the proximity effects due to e-beam lithography. For a nanohole array with a period of 100 nm and a diameter of 20 nm the corresponding bandgap is about 0.16 eV, but this parameter increases to 0.2 eV if the nanohole diameter becomes 30 nm. As a result, the charge carriers are guided through the central part of the channel and recombinations at channel boundaries are strongly reduced.

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Thank you !

Romanian Research Centre for Carbon Based Nanomaterials – Electronics at atomic scale.



